



PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:	)	
Wen-Ben CHOU et al.	)	Docket No. LAM2P295
Application No. 09/998,858	)	Examiner: Chen, Kin Chan
Filed: October 31, 2001	)	Group Art Unit: 1765
For: METHOD AND APPARATUS FOR	)	Date: April 24, 2003
NITRIDE SPACER ETCH PROCESS	)	
IMPLEMENTING <i>IN SITU</i> INTERFER-	)	
OMETRY ENDPOINT DETECTION	)	
AND NON-INTERFEROMETRY	)	
ENDPOINT MONITORING	)	

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service as First Class Mail in an envelope addressed to: Commissioner for Patents, Washington, DC 20231 on April 24, 2003.

Signed:

Diane Schwanbeck

ELECTION OF CLAIMS FOR PROSECUTION ON THE MERITS

Commissioner for Patents  
Washington, D.C. 20231

Dear Sir:

In response to the Restriction Requirement dated March 27, 2003, Applicants hereby elect, without traverse, **claims 1-16** (the Group I claims) for prosecution on the merits.

Applicants respectfully request examination on the merits for the subject application. Applicants believe that no fees are required in the filing of this Response; however, if any fees are due to effect consideration of this paper, then the Commissioner is authorized to charge such fees to Deposit Account No. 50-0805 (Order No. LAM2P295).

Respectfully submitted,  
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